

Appl. No. : 10/672,469
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IN THE ABSTRACT:

Please amend the abstract of the disclosure as follows:

An electron beam exposure apparatus for exposing a wafer by an electron beam incorporates a circuit structure for conducting a scan test to self-diagnose the electrical connections. The electron beam exposure apparatus includes: an electron beam generating section for generating the electron beam; a deflector plurality of deflectors for deflecting the electron beam corresponding electron beams; a deflection control section for outputting a deflection control signal for causing the deflector to deflect the electron beam; and a control signal storage section for storing a value of the deflection control signal output from the deflection control section. The control signal storage section connects the plurality of deflectors in series when conducting the scan test. The control signal storage section and the deflector may be monolithically integrated on a semiconductor substrate.